

Appl. No. : 09/997,396
Filed : November 28, 2001

IN THE CLAIMS

Please add the following new claim:

51. A method of reducing oxidized ferromagnetic metal in a magnetic structure into elemental metal comprising contacting the oxidized metal with a volatile organic compound selected from the group consisting of alcohols, aldehydes and carboxylic acids.

REMARKS

Applicants have amended the specification to correspond with the reference numerals used in revised Figure 3, submitted concurrently herewith in the Submission of Drawing Corrections for Approval by Examiner. The original reference numerals in Figure 3 were inadvertently used with different meaning in Figure 4. The present amendments correct this confusion. Applicants respectfully submit that the amendments introduce no new matter.

In addition Applicants have added new Claim 51. This claim was originally present between Claims 45 and 46 but was inadvertently not numbered.

In view of the foregoing amendments and remarks, Applicants submit that the application is in condition for examination on the merits and respectfully request the same.

Attached hereto is a separate paper entitled "VERSION SHOWING MARK-UP OF AMENDMENT SPECIFICATION PARAGRAPHS".

Respectfully submitted,

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VERSION SHOWING MARK-UP OF AMENDMENT SPECIFICATION PARAGRAPHS

Additions are shown in underlining.

Paragraph [57] has been amended as follows:

[0057] Figure 3 depicts a basic two-phase process for atomic layer deposition. Source chemical pulses 440 and 444 are separated from one another in time and space by purge periods 442 and 446. Alternatively, the purge periods can be replaced by evacuation of the chamber to remove byproduct and excess reactant between source chemical pulses 440, 444. Importantly, each pulse preferably has a self-limiting effect, leaving no more than about one molecular monolayer of material per cycle. Typically, the metal source chemicals include ligands that self-terminate adsorption of a monolayer or partial monolayer.

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